# Monthly LabAdviser update: 23/1 2017

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| Updated Subject | Contributor | Link to the updated pages |
| **Dry etch of SiO2 with hard masks.**  Etch selectivities using some recipes on AOE and ICP metal, with Cr, Al, Psi and Al2O3 as masking material  All work in process2share:  On AOE with recipe SiO2\_res  On AOE with recipe SiO2\_met  On AOE with a variation of SiO2\_pSi  On ICP metal with recipe: SiO2 etch with C4F8 | **Martin Lind Ommen @nanotech** | <http://process2share.danchip.dtu.dk/index.php/Specific_Process_Knowledge/Etch/Etching_of_SiO2>  [Standard\_recipe\_with\_resist\_mask#The\_standard\_recipe](http://labadviser.danchip.dtu.dk/index.php/Specific_Process_Knowledge/Etch/Etching_of_Silicon_Oxide/SiO2_etch_using_AOE/Standard_recipe_with_resist_mask#The_standard_recipe)  [SiO2\_etch\_using\_AOE/With\_Hard\_Mask](http://labadviser.danchip.dtu.dk/index.php/Specific_Process_Knowledge/Etch/Etching_of_Silicon_Oxide/SiO2_etch_using_AOE/With_Hard_Mask)  [SiO2\_etch\_using\_AOE/PolySi\_mask#Low\_line\_width\_reduction\_recipe](http://labadviser.danchip.dtu.dk/index.php/Specific_Process_Knowledge/Etch/Etching_of_Silicon_Oxide/SiO2_etch_using_AOE/PolySi_mask#Low_line_width_reduction_recipe)  [ICP\_Metal\_Etcher/silicon\_oxide#SiO2\_etch\_using\_DUV\_mask](http://labadviser.danchip.dtu.dk/index.php/Specific_Process_Knowledge/Etch/ICP_Metal_Etcher/silicon_oxide#SiO2_etch_using_DUV_mask) |
| **Deposition of NiV**  Has been added to Wordentec and tested.  Also new page on NiV in Lesker | **Patama Pholprasit @danchip** | [Thin\_film\_deposition/Deposition\_of\_NiV](http://labadviser.danchip.dtu.dk/index.php/Specific_Process_Knowledge/Thin_film_deposition/Deposition_of_NiV)  [Sputtering\_of\_NiV\_in\_Wordentec](http://labadviser.danchip.dtu.dk/index.php/Specific_Process_Knowledge/Thin_film_deposition/Deposition_of_NiV/Sputtering_of_NiV_in_Wordentec)  [Sputtering\_of\_NiV\_in\_Lesker](http://labadviser.danchip.dtu.dk/index.php/Specific_Process_Knowledge/Thin_film_deposition/Deposition_of_NiV/Sputtering_of_NiV_in_Lesker) |

# Equipment Manuals updated in LabManager:

As an approved user on a piece of equipment you have to make sure you have read and understood the latest version of the manual before using the equipment.

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